

**PARTIAL EDGE BEAD REMOVAL TO ALLOW
IMPROVED GROUNDING DURING E-BEAM MASK WRITING**

ABSTRACT OF THE DISCLOSURE

5 A method to provide a ground point for second, or subsequent, e-beam mask-writing steps by selectively removing the photoresist edge bead of a photomask substrate to expose the underlying chrome layer. The selective removal leaves at least one tab of photoresist edge bead over the chrome layer. After the first e-beam mask writing step and subsequent etch, the tab can be removed to expose a portion of the chromium layer that can act as a new ground point for a second e-beam etch. Also, a nozzle for use in selectively removing the edge bead to leave a tab of photoresist edge bead.